

ductruong

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COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.21	0.21

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FILE 'USPATOLD' ENTERED AT 15:54:02 ON 20 OCT 2008

CA INDEXING COPYRIGHT (C) 2008 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPAT2' ENTERED AT 15:54:02 ON 20 OCT 2008

CA INDEXING COPYRIGHT (C) 2008 AMERICAN CHEMICAL SOCIETY (ACS)

=> s polyarylene ether compound contsining sulfonic acid group#

L1 0 POLYARYLENE ETHER COMPOUND CONTSINING SULFONIC ACID GROUP#

=> s polyarylene ether compound containing sulfonic acid group#

L2 3 POLYARYLENE ETHER COMPOUND CONTAINING SULFONIC ACID GROUP#

=> d 12 1-3

L2 ANSWER 1 OF 3 EPFULL COPYRIGHT 2008 EPO/FIZ KA on STN

AN 2003:108255 EPFULL

DUPD 20040616 DUPW 200425

TIEN POLYARYLENE ETHER COMPOUND

CONTAINING SULFONIC ACID GROUP,

COMPOSITION CONTAINING SAME, AND METHOD FOR MANUFACTURING THOSE.

TIFR COMPOSE DE POLYARYLENE ETHER CONTENANT UN GROUPE ACIDE SULFONIQUE,

COMPOSITION LE CONTENANT ET PROCEDE POUR LEUR FABRICATION.

IN Sakaguchi, Yoshimitsu, Toyo Boseki K. K. Res. Ctr, 1-1 Katata 2-chome,

Otsu-shi, Shiga 520-0292, JP;

Kitamura, Kota, Toyo Boseki K. K. Research Ctr., 1-1 Katata 2-chome,

Otsu-shi, Shiga 520-0292, JP;

Nagahara, Shigenori, Toyo Boseki K. K. Res. Ctr., 1-1 Katata 2-chome,

Otsu-shi, Shiga 520-0292, JP;

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Yamashita, Masahiro, Toyo Boseki K. K. Res. Ctr., 1-1 Katata 2-chome,
Otsu-shi, Shiga 520-0292, JP;
Nakao, Junko, Sugihara, 265 Kitajima, Wakayama-shi, Wakayama 640-8403,
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PA Toyo Boseki Kabushiki Kaisha, (Boseki Kabushiki Kaisha, Toyo), 2-8,
Dojimahama 2-chome, Kita-ku, Osaka-shi, Osaka 530-8230, JP
PAN 1130871
DT Patent
LAF Japanese
LA English
LAP English
TL English; French
PIT WOAl International application published with search report
PI WO 2004033534 A1 20040422
DS AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HU IE IT LI LU MC NL PT RO SE
SI SK TR
EXTENSION STATES: AL LT LV MK
AI EP 2003-748749 A 20031007
WO 2003-JP12850 A 20031007
PRAI JP 2002-295284 A 20021008
JP 2003-32621 A 20030210
JP 2003-32622 A 20030210
IC.VER 7
ICM C08G065-40
ICS C09J171-08; H01M008-02; H01M008-10
AN 2003:108255 EPFULL ED 20050810 UP 20070816
DUPD 20070815 DUPW 200733
TIEN POLYARYLENE ETHER COMPOUND
CONTAINING SULFONIC ACID GROUP,
COMPOSITION CONTAINING SAME, AND METHOD FOR MANUFACTURING THOSE.
TIFR COMPOSE DE POLYARYLENE ETHER CONTENANT UN GROUPE ACIDE SULFONIQUE,
COMPOSITION LE CONTENANT ET PROCEDE POUR LEUR FABRICATION.
TIDE SULFONSuUREGRUPPENHALTIGE POLYARYLENETHER-VERBINDUNG, DIESE ENTHALTENDE
ZUSAMMENSETZUNG UND VERFAHREN ZU DEREN HERSTELLUNG.
IN Sakaguchi, Yoshimitsu, Toyo Boseki K. K. Res. Ctr, 1-1 Katata 2-chome,
Otsu-shi, Shiga 520-0292, JP;
Kitamura, Kota, Toyo Boseki K. K. Research Ctr., 1-1 Katata 2-chome,
Otsu-shi, Shiga 520-0292, JP;
Nagahara, Shigenori, Toyo Boseki K. K. Res. Ctr., 1-1 Katata 2-chome,
Otsu-shi, Shiga 520-0292, JP;
Yamashita, Masahiro, Toyo Boseki K. K. Res. Ctr., 1-1 Katata 2-chome,
Otsu-shi, Shiga 520-0292, JP;
Nakao, Junko, Sugihara, 265 Kitajima, Wakayama-shi, Wakayama 640-8403, JP
PA Toyo Boseki Kabushiki Kaisha, 2-8, Dojimahama 2-chome, Kita-ku,
Osaka-shi, Osaka 530-8230, JP
PAN 1130871
AG Mueller-Bore & Partner Patentanwaelte, Grafinger Strasse 2, 81671
Muenchen, DE
AGN 100651
DT Patent
LAF Japanese
LA English
LAP English
TL German; English; French
PIT EPA1 Application published with search report
PI EP 1561768 A1 20050810
WO 2004033534 20040422
DS AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HU IE IT LI LU MC NL PT RO SE

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SI SK TR
AI EP 2003-748749 A 20031007
WO 2003-JP12850 A 20031007
PRAI JP 2002-295284 A 20021008
JP 2003-32621 A 20030210
JP 2003-32622 A 20030210
IPCI C08G0065-40 [I,A]; C09J0171-08 [I,A]; H01M0008-02 [I,A]; H01M0008-10
[I,A]
C08G0065-00 [I,C*]; C09J0171-00 [I,C*]; H01M0008-02 [I,C*]; H01M0008-10
[I,C*]
L2 ANSWER 2 OF 3 PCTFULL COPYRIGHT 2008 Univentio on STN
AN 2004033534 PCTFULL ED 20040427 EW 200417
TIEN POLYARYLENE ETHER COMPOUND
CONTAINING SULFONIC ACID GROUP,
COMPOSITION CONTAINING SAME, AND METHOD FOR MANUFACTURING THOSE
TIFR COMPOSE DE POLYARYLENE ETHER CONTENANT UN GROUPE ACIDE SULFONIQUE,
COMPOSITION LE CONTENANT ET PROCEDE POUR LEUR FABRICATION
IN SAKAGUCHI, Yoshimitsu, Toyo Boseki Kabushiki Kaisha Research Center,
1-1, Katata 2-chome, Otsu-shi, Shiga 520-0292, JP [JP, JP];
KITAMURA, Kota, Toyo Boseki Kabushiki Kaisah Research Center, 1-1,
Katata 2-chome, Otsu-shi, Shiga 520-0292, JP [JP, JP];
NAGAHARA, Shigenori, Toyo Boseki Kabushiki Kaisha Research Center, 1-1,
Katata 2-chome, Otsu-shi, Shiga 520-0292, JP [JP, JP];
YAMASHITA, Masahiro, Toyo Boseki Kabushiki Kaisha Research Center, 1-1,
Katata 2-chome, Otsu-shi, Shiga 520-0292, JP [JP, JP];
NAKAO, Junko, Sugihara, 265, Kitajima, Wakayama-shi, Wakayama 640-8403,
JP [JP, JP]
PA TOYO BOSEKI KABUSHIKI KAISHA, 2-8, Dojimahama 2-chome, Kita-ku,
Osaka-shi, Osaka 530-8230, JP [JP, JP], for all designates States except
US;
SAKAGUCHI, Yoshimitsu, Toyo Boseki Kabushiki Kaisha Research Center,
1-1, Katata 2-chome, Otsu-shi, Shiga 520-0292, JP [JP, JP], for US only;
KITAMURA, Kota, Toyo Boseki Kabushiki Kaisah Research Center, 1-1,
Katata 2-chome, Otsu-shi, Shiga 520-0292, JP [JP, JP], for US only;
NAGAHARA, Shigenori, Toyo Boseki Kabushiki Kaisha Research Center, 1-1,
Katata 2-chome, Otsu-shi, Shiga 520-0292, JP [JP, JP], for US only;
YAMASHITA, Masahiro, Toyo Boseki Kabushiki Kaisha Research Center, 1-1,
Katata 2-chome, Otsu-shi, Shiga 520-0292, JP [JP, JP], for US only;
NAKAO, Junko, Sugihara, 265, Kitajima, Wakayama-shi, Wakayama 640-8403,
JP [JP, JP], for US only
AG FUKAMI, Hisao, Fukami Patent Office, Mitsui Sumitomo Bank
Minamimorimachi Building, 1-29, Minamimorimachi 2-chome, Kita-ku,
Osaka-shi, Osaka 530-0054, JP
LAF Japanese
LA Japanese
DT Patent
PI WO 2004033534 A1 20040422
DS W: AE AG AL AM AT AU AZ BA BB BG BR BY BZ CA CH CN CO CR CU
CZ DE DK DM DZ EC EE EG ES FI GB GD GE GH GM HR HU ID IL
IN IS KE KG KR KZ LC LK LR LS LT LU LV MA MD MG MK MN MW
MX MZ NI NO NZ OM PG PH PL PT RO RU SC SD SE SG SK SL SY
TJ TM TN TR TT TZ UA UG US UZ VC VN YU ZA ZM ZW
RW (ARIPO): GH GM KE LS MW MZ SD SL SZ TZ UG ZM ZW
RW (EAPO): AM AZ BY KG KZ MD RU TJ TM
RW (EPO): AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HU IE IT LU MC
NL PT RO SE SI SK TR
RW (OAPI): BF BJ CF CG CI CM GA GN GQ GW ML MR NE SN TD TG
PRAI JP 2002-2002-295284 20021008

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JP 2003-2003-32621 20030210
JP 2003-2003-32622 20030210
AI WO 2003-JP12850 A 20031007
ICM C08G065-40
ICS C09J171-08; H01M008-02; H01M008-10

L2 ANSWER 3 OF 3 USPATFULL on STN
AN 2006:195293 USPATFULL
TI Polyarylene ether compound
containing sulfonic acid group,
composition containing same, and method for manufacturing those
IN Sakaguchi, Yoshimitsu, Otsu-shi, JAPAN
Kitamura, Kota, Otsu-shi, JAPAN
Nagahara, Shigenori, Otsu-shi, JAPAN
Yamashita, Masahiro, Otsu-shi, JAPAN
Nakao, Junko, Wakayama-shi, JAPAN
PI US 20060166048 A1 20060727
AI US 2003-530199 A1 20031007 (10)
WO 2003-JP12850 20031007
20050404 PCT 371 date
PRAI JP 2002-295284 20021008
JP 2003-32621 20030210
JP 2003-32622 20030210
DT Utility
FS APPLICATION
LN.CNT 2271
INCL INCLM: 429/012.000
INCLS: 528/171.000; 525/125.000
NCL NCLM: 429/012.000
NCLS: 525/125.000; 528/171.000
IC IPCI H01M0008-00 [I,A]; C08G0075-00 [I,A]
IPCR H01M0008-00 [I,A]; B01D0067-00 [I,C*]; B01D0067-00 [I,A];
B01D0071-00 [I,C*]; B01D0071-52 [I,A]; B01D0071-62 [I,A];
B01D0071-68 [I,A]; B01D0071-82 [I,A]; C08G0065-00 [I,C*];
C08G0065-40 [I,A]; C08G0075-00 [I,C]; C08G0075-00 [I,A];
C08L0071-00 [I,C*]; C08L0071-10 [I,A]; C08L0071-12 [N,A];
C08L0079-00 [I,C*]; C08L0079-04 [N,A]; C08L0079-08 [I,A];
C09J0171-00 [I,C*]; C09J0171-08 [I,A]; H01B0001-12 [I,C*];
H01B0001-12 [I,A]; H01M0004-86 [N,C*]; H01M0004-86 [N,A];
H01M0004-88 [I,C*]; H01M0004-88 [I,A]; H01M0004-90 [N,C*];
H01M0004-92 [N,A]; H01M0008-00 [I,C]; H01M0008-02 [I,C*];
H01M0008-02 [I,A]; H01M0008-10 [I,C*]; H01M0008-10 [I,A];
H01M0010-36 [I,C*]; H01M0010-40 [I,A]
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

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